

Claims

1. A processing method for implementing irradiation with a charged particle beam in such a manner that, when deposition processing or etching processing of a prescribed pattern is carried out using a charged particle beam apparatus, a region of the pattern to be processed is divided up into microscopic regions corresponding to the diameter of the beam, and the dose amount for each microscopic region becomes equal.
2. The processing method for implementing irradiation with a charged particle beam of claim 1, wherein the dose amount is regulated according to scanning frequency.
3. The processing method for implementing irradiation with a charged particle beam of claim 1, wherein processing of a plurality of patterns within the scanning region is carried out at the same time.
4. The processing method for implementing irradiation with a charged particle beam of claim 2, wherein processing of a plurality of patterns within the scanning region is carried out at the same time.
5. A scanning type charged particle beam apparatus comprising:
means for dividing a pattern to be processed by scanning the pattern with a beam into microscopic regions corresponding to the diameter of the beam and obtaining irradiation amount distribution information in the divided microscopic regions;
and means for regulating processing in such a manner that the

